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CLAIM AMENDMENTS

1. (Currently Amended) A chemical-mechanical polishing system comprising:
 - (a) a liquid carrier,
 - (b) a polishing component selected from the group consisting of (i) a polishing pad, (ii) an abrasive, and (iii) a polishing pad and an abrasive, and
 - (c) at least one amine-containing polymer with ~~about~~ 5 or more sequential atoms separating the nitrogen atoms of the amino functional groups.
2. (Original) The system of claim 1, wherein at least one amine-containing polymer is a condensation polymer comprising repeating units that contain an amino functional group.
3. (Original) The system of claim 2, wherein the condensation polymer is a polyaminoamide.
4. (Original) The system of claim 3, wherein the condensation polymer is a diethylenetriamine/adipic acid condensation polymer.
5. (Currently Amended) ~~The system of claim 1~~ A chemical-mechanical polishing system comprising:
 - (a) a liquid carrier,
 - (b) a polishing component selected from the group consisting of (i) a polishing pad, (ii) an abrasive, and (iii) a polishing pad and an abrasive, and
 - (c) at least one amine-containing polymer with 5 or more sequential atoms separating the nitrogen atoms of the amino functional groups,wherein at least one amine-containing polymer is polydiallyldimethylammonium chloride.
6. (Currently Amended) ~~The system of claim 1~~ A chemical-mechanical polishing system comprising:
 - (a) a liquid carrier,

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- (b) a polishing component selected from the group consisting of (i) a polishing pad, (ii) an abrasive, and (iii) a polishing pad and an abrasive, and
(c) at least one amine-containing polymer with 5 or more sequential atoms separating the nitrogen atoms of the amino functional groups,

wherein at least one amine-containing polymer is a copolymer comprising repeating units containing an amine functional group and repeating units selected from the group consisting of amides, vinyl acetate, ethylene oxide, and propylene oxide.

7. (Original) The system of claim 1, wherein at least one amine-containing polymer has about 7 or more sequential atoms separating the nitrogen atoms of the amino functional groups.
8. (Original) The system of claim 1, wherein at least one amine-containing polymer has about 10 or more sequential atoms separating the nitrogen atoms of the amino functional groups.
9. (Original) The system of claim 1, further comprising a per-type oxidizer.
10. (Original) The system of claim 9, wherein the per-type oxidizer is selected from the group consisting of peroxides, persulfates, periodates, and permanganates.
11. (Original) The system of claim 1, further comprising a complexing agent.
12. (Previously Presented) A chemical-mechanical polishing system comprising:
- (a) a liquid carrier,
 - (b) a polishing component selected from the group consisting of (i) a polishing pad, (ii) an abrasive, and (iii) a polishing pad and an abrasive, and
 - (c) at least one amine-containing block copolymer with at least one polymer block comprising one or more amine functional groups and at least one polymer block not comprising any amine functional groups.
13. (Original) The system of claim 12, wherein at least one amine-containing block copolymer is an AB diblock, ABA triblock, or ABC triblock copolymer.

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14. (Original) The system of claim 12, wherein the polymer blocks comprising one or more amine functional groups are about 10 wt.% or more of the amine-containing block copolymer.

15. (Original) The system of claim 14, wherein the polymer blocks comprising one or more amine functional groups are about 20 wt.% or more of the amine-containing block copolymer.

16. (Original) The system of claim 12, wherein the polymer block comprising one or more amine functional groups are about 40 wt.% or more of the amine-containing block copolymer.

17. (Original) The system of claim 12, wherein at least one amine-containing block has about 5 or more sequential atoms separating the nitrogen atoms of the amino functional groups.

18.-24. (Previously Canceled)

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